

Attorney's Docket No.: 05542-516001 / 7901/CMP

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Birang et al.

Art Unit : 2818

Serial No.: 10/721,769

Examiner: David Nhu

Filed

: November 24, 2003

September 7,2005

Title

: METHODS AND APPARATUS FOR POLISHING CONTROL

## MAIL STOP AMENDMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

## INFORMATION DISCLOSURE STATEMENT

Applicants request consideration of the references listed on the attached PTO-1449 form. Under 37 C.F.R. § 1.98 (a)(2)(ii), only copies of foreign patent documents and/or non-patent literature are enclosed. Copies of any listed U.S. patents or U.S. patent application publications can be provided upon request.

This statement is being filed after a first Office action on the merits, but before receipt of a final Office action or a Notice of Allowance. A check for \$180 in payment of the late submission fee of §1.17(p) is enclosed. Please apply any other appropriate charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

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CERTIFICATE OF MAILING BY FIRST CLASS MAIL

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Substitute Form TO-1449 (Modified)

U.S. Department of Commerce Patent and Trademark Office Attorney's Docket No. 05542-516001

Application No. 10/721,769

Information Disclosure Statement by Applicant (Use several sheets if necessary)

Applicant Birang et al.

Group Art Unit

2812

(37 CFR §1.98(b))

Filing Date November 24, 2003

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	5,081,796	01/1992	Schultz			
	AB	5,486,129	01/1996	Sandhu et al.			
	AC	5,658,183	08/1997	Sandhu et al.			
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	AK	6,413,145	07/2002	Pinson, II et al.			
	AL	6,422,927	07/2002	Zuniga			

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner	Desig.	Document	Publicatio	Country or			Transla	ation
Initial	ID	Number	n Date	Patent Office	Class	Subclass	Yes	No
	AM	DE 3801969 A	07/1989	DE			English Abstract	
-	AN	EP 0879678 A	11/1998	EPO				
	AO	EP 0904895 A	03/1999	EPO				

Other Documents (include Author, Title, Date, and Place of Publication)					
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	AP	Wijekoon et al., "Minimization of Metal Loss during Chemical Mechanical Planerization of Copper-Oxide and Copper – Low K Damascene Structures", March 2002, Santa Clara, CA, 4 pp.			
	AQ	Ravid et al., "Copper CMP Planarity Control Using ITM", 2000, Rehovoth, Israel, 7 pp.			
	AR	Pan et al., "Copper CMP and Process Control", Final Paper submitted to CMP-MIC Conference, February 11-12, 1999, Santa Clara, CA and Cambridge, MA, 7 pp.			
	AS	Zhang et al., "Automated Process Control of Within-Wafer and Wafter-to-Wafer Uniformity in Oxide CMP", March 2002, Santa Clara, CA, 6 pp.			

Examiner Signature	Date Considered				
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EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with					
next communication to applicant.					